

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

APPLICANT(S):

Hammond et al.

CONF. NO.:

2980

SERIAL NO.:

10/797,231

ART UNIT:

2812

FILING DATE:

March 10, 2004

EXAMINER:

Ghyka, Alexander G.

TITLE:

Method of Selective Removal of SiGe Alloys

Mail Stop Amendment Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Sir:

In accordance with the provisions of 37 C.F.R. § 1.97 and 1.98, Applicants hereby make of record the information contained herein, for consideration by the Examiner in connection with the examination of the above-identified patent application.

REMARKS

In accordance with the provisions of 37 C.F.R. 1.97, this statement is being filed (CHECK ONE):

	(1)	within three (3) months of the filing date of a national application other than a continued prosecution application under 37 C.F.R. 1.53(d), or within three (3) months of the date of entry of the national stage as set forth in 37 C.F.R. 1.491 in an international application, or before the mailing of the first Office action on the merits, or before the mailing of a first Office action after the filing of a request for continued examination under 37 C.F.R. 1.114; or
\boxtimes	(2)	after the period defined in (1) but before the mailing date of a final action or a notice of allowance under 37 C.F.R. 1.311, and
		the requisite Statement is below, OR
	\boxtimes	the requisite fee under 37 C.F.R. 1.17(p), namely \$180.00, is included herein, or
	(3)	after the mailing date of a final action or notice of allowance but before the payment of the issue fee , AND

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Supplemental Information Disclosure Statement
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the requisite Statement is below, AND

the requisite petition fee under 37 C.F.R. 1.17(p), namely \$180.00 is included herein.

Pursuant to MPEP section 2001.06(c), applicants hereby apprise the U.S. Patent and

Trademark Office that the parent of the instant application is currently the subject of a litigation

It is respectfully requested that the information contained herein be made of record in this application.

captioned AmberWave Systems Corporation v. Intel Corporation, Civil Action No. 05-837-KAJ.

Date: <u>Argust 16, 2006</u> Reg. No. 58,533

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LIBC/2825963.1

Respectfully submitted,

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ATTORNEY DOCKET NO.: ASC-057C1 FORM PTO - 1449 Hammond et al. APPLICANT(S): SECOND SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT 10/797,231 SERIAL NO.: FILING DATE: March 10, 2004 GROUP: 2812 U.S. PATENT DOCUMENTS CLASS SUB FILING DATE IF DOCUMENT DATE NAME EXAM. APPROPRIATE CLASS INIT. NUMBER A67 5,417,180 5/23/1995 Nakamura FOREIGN PATENT DOCUMENTS **ENGLISH DOCUMENT** DATE COUNTRY CLASS SUB FILING **ABSTRACT** EXAM. CODE CLASS DATE ONLY LANG INIT. NUMBER (Y/N) OTHER ART, JOURNAL ARTICLES, ETC. EXAM. OTHER DOCUMENTS: (Including Author, Title, Date, Relevant Pages, Place of Publication) INIT. Chang, G.K., et al., "Selective Etching of SiGe on SiGe/Se Heterostructures," J. ELECTROCHEM. SOC. (1999) 138(1):202-04. Ismail, K., "Si/SiGe High-Speed Field Effect Transistors," IEEE IEDM TECH. DIG. (1995) 509-12. C75 LeGoues, F.K. et al., "Oxidation studies of SiGe," J. APPL. PHYS. (1989) 65(4): 1724-28. C76 Rhee, S.S., et al., "SiGe Resonant Tunneling Hot Carrier Transistor," IEEE IEDM TECH. DIG. (1999) C77 C78 Wolf, S., SILICON PROCESSING FOR THE VLSI ERA: VOL.2-PROCESS INTEGRATION (1990) Lattice Press, 66-83.

DATE CONSIDERED

LIBC/2825814.1

EXAMINER